

Amendments to the Specification:

Please replace paragraphs [00012] and [00013] with the following amended paragraphs:

[00012] The process chamber base 4 mentioned is formed substantially by a substrate holder carrier 3, which is a rotationally driven plate which may consist of the same material as the process chamber cover 5. The process chamber base 4 may consist of graphite, metal, quartz or ceramic. As illustrated in Figure 3, the substrate holder carrier 3 may, in some embodiments, comprise more than one part, and be held centrally by two clamping plates 11, 12. In such embodiments, the center plate 7 preferably lies above an uppermost of the two clamping plates 11.

[00013] The substrate holder carrier 3 has a number of pot-shaped recesses disposed in circumferentially equal distribution at the same radial distance from the center. Channels 21 open into these pot-shaped recesses in the form of nozzles 23. The configuration of the nozzles is described by US Patent 4860687. Reference is made to this document in this respect. The nozzles 23 are configured in such a way that the circular-disk-shaped substrate holders 2 lying in the pot-shaped recesses are rotationally driven about axes 18 by the gas stream emerging from the nozzles 23. The substrate holders 2 lie on a gas cushion. The substrate holders 2 are located in a peripheral zone 4" of the base 4. This zone corresponds to the diffusion zone in the gas phase lying there above. From this zone, the decomposition products produced in a decomposition zone lying in the center region are to be transported, in order to reach the substrate.